

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant	:	Hojo et al.
Appl. No.	:	10/553,083
Filed	:	October 11, 2005
For	:	POSITIVE RESIST COMPOSITION AND METHOD OF FORMATION OF RESIST PATTERN
Examiner	:	C. Hamilton
Group Art Unit	:	1752

**AMENDMENT AND RESPONSE TO OFFICE ACTION**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed **July 3, 2007**, Applicants respectfully request the Examiner to enter the following amendments and consider the following remarks.

**The listing of claims** begins on page 2 of this paper. The claims are provided for the Examiner's convenience. No amendments have been made.

**Remarks** begin on page 5 of this paper.